

ABSTRACT

5 A resist composition is provided comprising a
fluorochemical surfactant which functions to reduce the
contact angle of a coating of the resist composition with
water or an aqueous base developer as the amount of the
fluorochemical surfactant increases. The resist
composition forms a coating having a thickness uniformity,
10 free of defects, and wettable with an aqueous base
developer when applied onto a substrate, and has a good
storage stability in that particles do not increase during
storage in solution form.

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